Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2423	430/322.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 11:03
S71	2	("6835525").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/19 11:05
S73	2	("6890697").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/19 11:06
S72	2	("6861199").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/19 11:06
S76	86582	formic adj acid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/03/19 12:32
S74	2	("6165680").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/19 12:32
S12	1766	chemical\$4 same amplified same positive same resist	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 12:32
S79	1900	chemical\$4 same amplified same positive same resist	US-PGPUB; USPAT;. USOCR; EPO; JPO	OR	ON	2007/03/19 12:33

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S78	805	S76 same S77	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 12:33
S77	818570	photoresist or resist or photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 12:33
S80	6	S78 and S79	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 12:38
S81	2486	430/322.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 13:22
S86	21	irradiat\$4 same expos\$3 same light same brewster same angle	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 13:26
S85	245	S81 and S84	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON .	2007/03/19 13:26
S84	6013	430/270.1.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 13:26
S83	61	S82 and develop\$4	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 13:26
S82	70	chemical\$4 same amplify same resist	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/19 13:26
S87	5452	styrene adj sulfonic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN	OR	ON .	2007/03/19 14:33
	,		T; IBM_TDB			

S88	5369	styrene adj sulfonic adj acid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/03/19 14:34
S70	2	("6828083").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/19 14:34
S90	58	S88 same S77	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/03/19 14:35
S36	68	chemical\$4 same amplify same resist	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/20 11:27
S97	818922	resist or photoresist or photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/20 11:28
S98	26	S97 and S93	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/20 11:29
S94	70	chemical\$4 same amplify same resist	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/20 11:56
S91		styrenesulfonic adj acid adj ester	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/03/20 13:12

S99	. 2	("5585220").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/20 13:13
S100	2	("6303263").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/20 13:14
S93	26	(polystyrenesulfonic adj acid) and (pattern adj formation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/03/20 15:06
S104	1	"20020012870".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON ,	2007/03/20 15:08
S107	1	"20050191576".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	ON	2007/03/20 15:15
S110	2	("5403467").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/20 15:19
S109	2	("6531618").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	OFF	2007/03/20 15:19